

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	254984	(remov\$3 or stripp\$3 or etch\$3) same oxide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/21 08:31
L3	320	2 same ((transfer\$3 or load adj lock) near chamber)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/21 08:33
L4	219	3 same (wafer or semiconductor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/21 08:33
L5	101	4 and @pd<"20010111"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/21 08:50
L6	32	4 same ((vapor\$3 near solution) or (hydrofluoric or "HF"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/21 09:17
L7	3	pas-sylvia-h.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/11/21 09:17